

ION BEAM IRRADIATION OF COPPER NITRIDE: THE NITROGEN DEPLETION MECHANISM

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Introduction

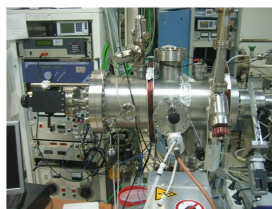
Copper nitride is a metastable material which results very attractive because of their potential to be used in functional device. Cu_3N easily decomposes into Cu and N_2 by annealing [1] or irradiation (electron, ions, laser) [2, 3].

Previous studies carried out in N-rich Cu_3N films irradiated with Cu at 42 MeV evidence a very efficient sputtering of N whose yield (5×10^3 atom/ion), for a film with a thickness of just 100 nm, suggest that the origin of the sputtering has an electronic nature. This N depletion was observed to be responsible for new phase formation (Cu_2O) and pure Cu [4].

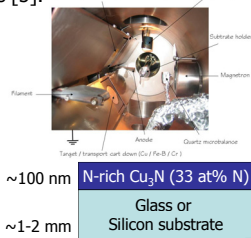
Experimental Description

Samples deposition: DC Triode Sputtering

Polycrystalline N-rich Cu_3N films with a thickness of ~ 100 nm were deposited by DC-triode sputtering from a Cu target in the presence of a $\text{N}_2 + \text{Ar}$ atmospheres [5].



Sputtering chamber at the IMM/CSIC



~ 100 nm N-rich Cu_3N (33 at% N)
Glass or Silicon substrate
 $\sim 1-2$ mm

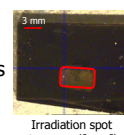
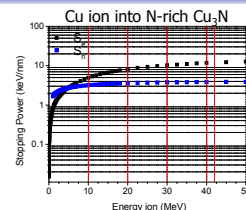
Ion beam modification and characterization

- Samples were irradiated with Cu ions at different energies from 42 MeV ($S_e = 12.48$ keV/nm) to 10 MeV ($S_e = 4.93$ keV/nm).
- At fluences from 4×10^{11} ion/cm² up to 4.5×10^{14} ion/cm², covering from the single ion track to the overlapping track regime.
- Some of the samples were irradiated with Cu at 42 MeV at different substrate temperatures ($100^\circ\text{C} < T < 300^\circ\text{C}$).
- Nitrogen depletion is monitored by means of IBA techniques (NRA and ERDA).

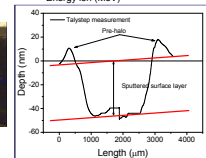
Objectives

Our present aims are:

- To elucidate the responsible mechanism for the nitrogen losses.
- To determine the stopping power threshold for N depletion



Irradiation spot ($\Phi = 4 \times 10^{13} \text{ cm}^{-2}$)



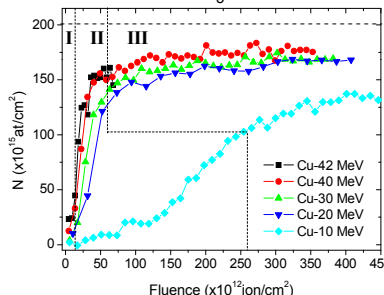
Profilometry measurement of the height of the beam spot profile

Results

N depletion: influence of stopping power (S_e)

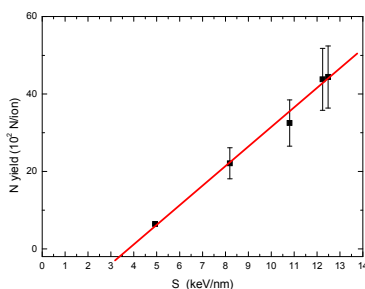
The characterisation of N depletion as a function of stopping power allows determining the S_e threshold for N depletion.

N-rich Cu_3N /Glass



Three regions can be distinguished in the process of nitrogen escape:

- Region I:** The N content is almost constant \Rightarrow the migration and N_2 formation might be hampered by N trapping
- Region II:** High N sputtering rate which rapidly increase with rising $S_e \Rightarrow$ N migration > N trapping
- Region III:** No N depletion is observed \Rightarrow The N content in the sample is almost exhausted



- Yield strongly increases with S_e beyond a threshold value of 3.5 KeV/nm
- $Y_{\text{measured}} \gg 0.16 \text{ N/at}$ for Cu@42 MeV (calculated with SRIM)

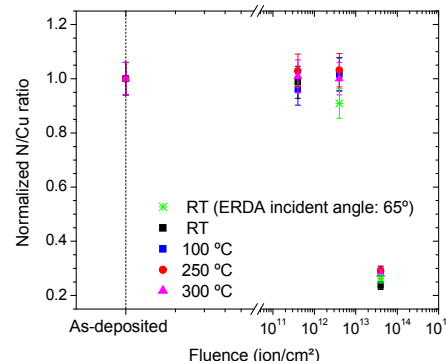


Electronic processes

Conclusions

- A high N depletion yield has been observed at intermediates radiation fluence.
- The number of N sputtered atoms very strongly increases with rising the electronic stopping power.
- The N depletion has been demonstrated not to depend on substrate temperature during irradiation.
- A stopping power threshold of 3.5 KeV/nm is determines for N depletion. This results is very important since it can be extrapolated to other irradiation techniques such as laser.
- All the data point out that the N depletion mechanism has an electronic nature and the excitonic model might account for the experimental observations.

N depletion: influence of the substrate Temperature during irradiation



- No dependence of nitrogen depletion on the substrate temperature during irradiation is observed.
- These data cannot be properly explained on the basis of any of the existing thermal spike models [7, 8] because any of them would predict a significant track radius enhancement with increasing irradiation temperature, which would result in an increase in the nitrogen sputtering rate \Rightarrow but they can be better explained by considering the **excitonic model**.

References

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